

efficiently carry out the exposure method of the present invention.

Page 13, line 16 to page 14, line 2, delete current paragraph and insert therefor:

A7
In still another aspect, a method for producing a device according to the present invention resides in a method for producing a device, comprising the step of transferring a device pattern onto a workpiece by using the exposure method of the present invention or the exposure apparatus of the present invention. When the exposure method of the present invention is used, then the transmittance of the optical path for the exposure light beam is maintained to be high, and the illuminance (exposure energy) of the exposure light beam on the workpiece is maintained to be high. Therefore, the throughput of the exposure step is improved, and it is possible to produce the device at the high throughput.

Page 18, line 7:

DETAILED DESCRIPTION OF EXEMPLARY EMBODIMENTS

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IN THE CLAIMS:

Please replace claims 14-15 as follows:

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14. (Amended) A method for producing a device, comprising the step of transferring a device pattern onto a workpiece by using the exposure method as defined in claim 1.

15. (Amended) A method for producing a device, comprising the step of transferring a device pattern onto a workpiece by using the exposure apparatus as defined in claim 5.

Please add new claims 21-25 as follows:

A10
--21. A method for producing a device, comprising the step of transferring a device pattern onto a workpiece by using the exposure method as defined in claim 3.--

--22. A method for producing a device, comprising the step of transferring a device pattern onto a workpiece by using the exposure apparatus as defined in claim 8.--

--23. A method for producing a device, comprising the step of transferring a device